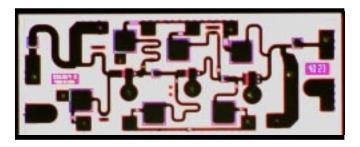


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Ka Band Wideband LNA/Driver

TGA1319C-EPU



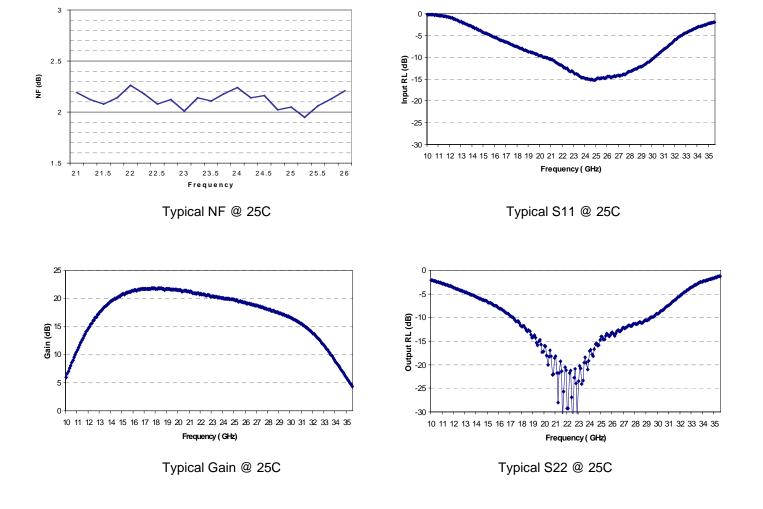
Chip Dimensions 2.179 mm x .847 mm

Key Features and Performance

- 0.15um pHEMT Technology
- 16-30 GHz Frequency Range
- 2.25 dB Nominal Noise Figure midband
- 21 dB Nominal Gain
- 14 dBm Pout
- Bias 5V, 60 mA with -0.5V < Vg < +0.5V

Primary Applications

- Point-to-Point Radio
- Point-to-Multipoint Communications



Note: Devices designated as EPU are typically early in their characterization process prior to finalizing all electrical and process specifications. Specifications subject to change without notice



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MAXIMUM RATINGS

SYMBOL	PARAMETER 4/	VALUE	NOTES
\mathbf{V}^+	POSITIVE SUPPLY VOLTAGE	9 V	
\mathbf{I}^+	POSITIVE SUPPLY CURRENT	80 mA	<u>1</u> /
I	NEGATIVE GATE CURRENT	5.28 mA	
P _{IN}	INPUT CONTINUOUS WAVE POWER	18 dBm	
P _D	POWER DISSIPATION	.72 W	
T _{CH}	OPERATING CHANNEL TEMPERATURE	150 ⁰ C	<u>2/3/</u>
T_{M}	MOUNTING TEMPERATURE (30 SECONDS)	320 °C	
T _{STG}	STORAGE TEMPERATURE	-65 to 150 °C	

- $\underline{1}$ / Total current for all stages.
- 2/ These ratings apply to each individual FET.
- $\underline{3}$ / Junction operating temperature will directly affect the device median time to failure (T_M). For maximum life, it is recommended that junction temperatures be maintained at the lowest possible levels.
- $\underline{4}$ / These ratings represent the maximum operable values for the device.

DC PROBE TESTS ($T_A = 25 \text{ °C} \pm 5 \text{ °C}$)

Symbol	Parameter	Minimum	Maximum	Value
Idss	Saturated Drain Current			mA
V _P	Pinch-off Voltage	-1.5	-0.5	V
BVGS	Breakdown Voltage gate-source			V
BVGD	Breakdown Voltage gate-drain			V

ON-WAFER RF PROBE CHARACTERISTICS $(T_A = 25 \text{ °C} \pm 5 \text{ °C})$

 $V_{d}=5 \ V, \ I_{d1}=10 \ mA, \ I_{d2}=50 \ mA$

Symbol	Parameter	Test Condition	Limit		Units	
			Min	Тур	Max	
Gain	Small Signal Gain	F = 21 - 27 GHz	19			dB
NF	Noise Figure	F = 21 - 25 GHz			2.5	dB
		F = 26 - 26.5 GHz			2	
PWR	Output Power	F = 21 - 26 GHz	10			dBm
	@ P1dB	F = 27 GHz	9			

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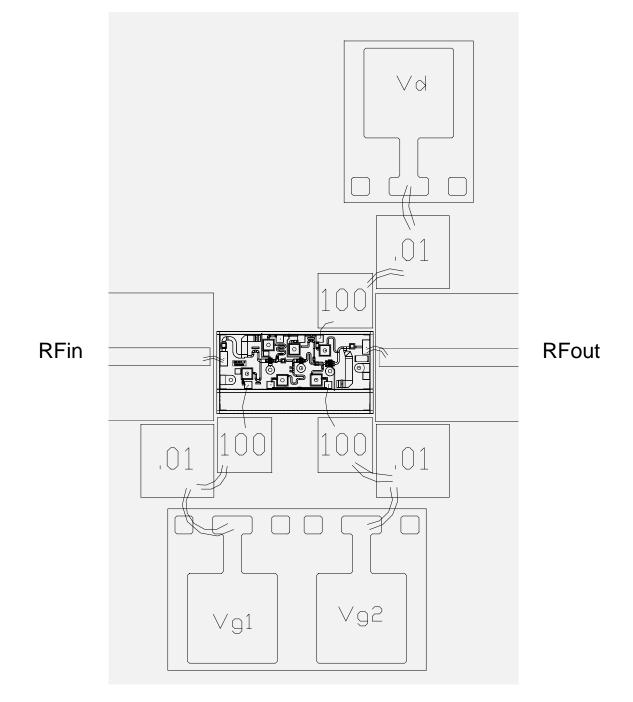
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Notes:1. Vg1 and Vg2 may be sourced from the same supply.

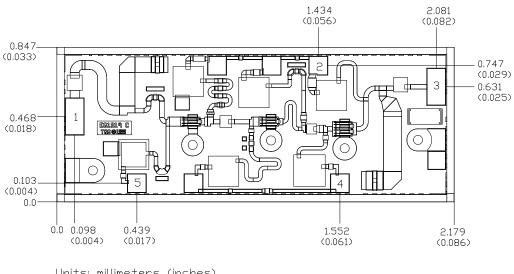
2. Positive or negative gate bias may be required to achieve recommended operating point.

TGA1319C- Recommended Assembly Drawing

Note: Devices designated as EPU are typically early in their characterization process prior to finalizing all electrical and process specifications. Specifications subject to change without notice



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Units: millimeters (inches) Thickness: 0.1016 (0.004) Chip edge to bond pad dimensions are shown to center of bond pad Chip size tolerance: +/- 0.051 (0.002)

Bond Pad #	#1 (RF Input)	$0.100 \times$	0.200	(0.004	×	0.008>
Bond Pad #	#2 (Vd)	$0.100 \times$	0.100	(0.004	×	0.004)
Bond Pad #	#3 (RF Output)	$0.100 \times$	0.200	(0.004	×	0.008)
Bond Pad #	#4 (Vg2)	$0.100 \times$	0.100	(0.004	×	0.004)
Bond Pad f	#5 (Vg1)	0.100 \times	0.100	(0.004	×	0.004>

Mechanical Drawing

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Assembly Process Notes

Reflow process assembly notes:

- Use AuSn (80/20) solder with limited exposure to temperatures at or above 300 °C.
- An alloy station or conveyor furnace with reducing atmosphere should be used.
- No fluxes should be utilized.
- Coefficient of thermal expansion matching is critical for long-term reliability.
- Devices must be stored in a dry nitrogen atmosphere.

Component placement and adhesive attachment assembly notes:

- Vacuum pencils and/or vacuum collets are the preferred method of pick up.
- Air bridges must be avoided during placement.
- The force impact is critical during auto placement.
- Organic attachment can be used in low-power applications.
- Curing should be done in a convection oven; proper exhaust is a safety concern.
- Microwave or radiant curing should not be used because of differential heating.
- Coefficient of thermal expansion matching is critical.

Interconnect process assembly notes:

- Thermosonic ball bonding is the preferred interconnect technique.
- Force, time, and ultrasonics are critical parameters.
- Aluminum wire should not be used.
- Discrete FET devices with small pad sizes should be bonded with 0.0007-inch wire.
- Maximum stage temperature is 200°C.

GaAs MMIC devices are susceptible to damage from Electrostatic Discharge. Proper precautions should be observed during handling, assembly and test.

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